

United States Patent and Trademark Office

UNITED STATES DEPARTMENT OF COMMERCE United States Patent and Trademark Office Address: COMMISSIONER FOR PATENTS P.O. Box 1450 Alexandria, Virginia 22313-1450 www.uspto.gov

APPLICATION NO.		FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO
09/988,559		11/20/2001	Kenya Wada	216202US3	8756
40575	7590	03/17/2004		EXAMINER	
KCO LAV		C.	HASSANZADEH, PARVIZ		
P. O. BOX CHANTILI		20153-0472		ART UNIT PAPER NUMBER	
	,			1763	
				DATE MAIL ED: 02/17/200	4

Please find below and/or attached an Office communication concerning this application or proceeding.

			ALC:
	Application No.	Applicant(s)	
	09/988,559	WADA ET AL.	
Office Action Summary	Examiner	Art Unit	
	Parviz Hassanzadeh	1763	
The MAILING DATE of this communication a Period for Reply	ppears on the cover sheet with	the correspondence addre	SS
A SHORTENED STATUTORY PERIOD FOR REP THE MAILING DATE OF THIS COMMUNICATION - Extensions of time may be available under the provisions of 37 CFR after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a re - If NO period for reply is specified above, the maximum statutory perions - Failure to reply within the set or extended period for reply will, by state than three months after the mained patent term adjustment. See 37 CFR 1.704(b).	1. 1.136(a). In no event, however, may a reply eply within the statutory minimum of thirty (3 od will apply and will expire SIX (6) MONTH: ute, cause the application to become ABAN	be timely filed 10) days will be considered timely. S from the mailing date of this committed DONED (35 U.S.C. § 133).	unication.
Status			
1) ☐ Responsive to communication(s) filed on 16 2a) ☐ This action is FINAL. 2b) ☐ The 3) ☐ Since this application is in condition for allow closed in accordance with the practice under	nis action is non-final. vance except for formal matters	•	erits is
Disposition of Claims			
4) ☐ Claim(s) 1-11 is/are pending in the application 4a) Of the above claim(s) 5-11 is/are withdray 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1-4 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and	wn from consideration.		
Application Papers			
9) ☐ The specification is objected to by the Examination 10) ☐ The drawing(s) filed on 16 January 2004 is larger Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11) ☐ The oath or declaration is objected to by the	re: a)⊠ accepted or b)⊡ obje ne drawing(s) be held in abeyance ection is required if the drawing(s)	. See 37 CFR 1.85(a). is objected to. See 37 CFR 1	` '
Priority under 35 U.S.C. § 119			
a) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority docume 2. Certified copies of the priority docume 3. Copies of the certified copies of the prapplication from the International Bure * See the attached detailed Office action for a list	nts have been received. nts have been received in App iority documents have been re eau (PCT Rule 17.2(a)).	lication No ceived in this National Sta	ge
Attachment(s)			
 Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/0 Paper No(s)/Mail Date 	_	nmary (PTO-413) Mail Date mal Patent Application (PTO-15.	2)

Art Unit: 1763

DETAILED ACTION

Election/Restrictions

Applicant's election with traverse of Group I, method claims 1-4, in Paper No. 7 is acknowledged. The traversal is on the ground(s) that the method cannot be used for a stationary substrate and the search for the method claims would necessarily include search for the apparatus claims. This is not found persuasive because the claim 1 does not requires a moving substrate and the steps of removing oxygen, supplying humidified inert gas and irradiating the substrate can be performed on a stationary substrate; and the search required for the method claims are not necessarily coextensive with the search required for the apparatus claims.

The requirement is still deemed proper and is therefore made FINAL.

Claims 5-11 are withdrawn from further consideration pursuant to 37 CFR 1.142(b), as being drawn to a nonelected Group II, apparatus, there being no allowable generic or linking claim. Applicant timely traversed the restriction (election) requirement in Paper No. 7.

it is suggested to cancel the non-elected claims 5-11 in order to expedite the prosecution of the application.

Drawings

The drawing was received on 1/16/04. This drawing is acceptable by the Examiner.

Claim Rejections - 35 USC § 112

The following is a quotation of the first paragraph of 35 U.S.C. 112:

The specification shall contain a written description of the invention, and of the manner and process of making and using it, in such full, clear, concise, and exact terms as to enable any person skilled in the art to which it pertains, or with which it is most nearly connected, to make and use the same and shall set forth the best mode contemplated by the inventor of carrying out his invention.

Art Unit: 1763

Claims 1-4 are rejected under 35 U.S.C. 112, first paragraph, as based on a disclosure which is not enabling. The fact that "the substrate is treat in a treating chamber which is maintained at a reduced pressure as the substrate is transferred therethrough during the treating process" is critical or essential to the practice of the invention, but not included in the claim(s) is not enabled by the disclosure. See *In re Mayhew*, 527 F.2d 1229, 188 USPQ 356 (CCPA 1976). Page 9 of the specification describes the treating chamber 12 including an entrance opening 12a and an exit opening 12b for admitting in and sending out the substrate through the chamber, and on page 12, it further requires the chamber including an exhaust pipe 33 so that the negative pressure is maintained in the chamber during the treatment process.

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).

Claims 1-3 are rejected under 35 U.S.C. 103(a) as being unpatentable over Kinoshita et al (JP 2001-137800) in view of Kanai et al (US Patent No. 5,520,740).

Art Unit: 1763

Kinoshita et al teach a method for treating a surface of a substrate plate 10 as shown in Fig. 10 (front drawing) under irradiation of ultraviolet ray emitted from a dielectric barrier discharge lamp 1, the method comprising the steps of:

supplying humidified inert gas containing mixture of inert gas and water via feed pipe 15 toward the substrate 10 to humidify the treating surface and surrounding atmosphere of the substrate; and

irradiating the treating surface of the substrate with ultraviolet ray form the dielectric barrier discharge lamp1.

Kinoshita et al fail to teach removing oxygen on and in the vicinity of the treating surface of the substrate (abstract).

Kanai et al teach a method of treating the surface of a substrate wherein the surface of the substrate is purged using an inert gas such as Ar as the substrate is transferred into a processing chamber via a gate gas supply 1016 and the exhausted via exhaust pipe 1018 in order to sufficiently isolate vacuum vessel from each other (column 42, line 59 through column 43, line 14, column 52, lines 44-67).

Therefore, it would have been obvious to one of ordinary skill in the art at the time of the invention to implement the purging mechanism as taught by Kanai et al in the method of Kinoshita et al in order to isolated the treating chamber from the adjacent units. The purging mechanism would inherently remove oxygen on and in the vicinity of the treating surface of the substrate.

Regarding claim 2: the purging gas is an inert gas such as argon (Kanai et al, column 42, line 59 through column 43).

Art Unit: 1763

Regarding claim 3: the humidified inert gas mixture includes nitrogen (Kinoshita et al, paragraph 0012, 0021).

Claim 4 is rejected under 35 U.S.C. 103(a) as being unpatentable over Kinoshita et al (JP 2001-137800) in view of Kanai et al (US Patent No. 5,520,740) as applied to claims 1-3 above, and further in view of Laethem et al (US Patent No. 4,188,199).

Kinoshita et al in view of Kanai et al teach all limitations of the claims as discussed above except for the oxygen or air removing gas is introduced in opposite direction of the substrate transfer direction and the humidified inert gas is introduced obliquely in a forward direction of the substrate transfer direction.

Laethem et al teach a method of treating the surface of a continuously longitudinally moving substrate wherein the treating gases are introduced at an oblique angle and in the moving direction of the substrate as shown in Fig. 2 in order to improved uniform exposure of the surface of the substrate to treating gases (column 1, lines 38-60).

Therefore, it would have been obvious to one of ordinary skill in the art at the time of the invention to implement the oblique angle exposure mechanism as taught by Laethem et al in the method of Kinoshita et al in view of Kanai et al in order to improve the uniformity of the exposure of the treating gases with the surface of the moving substrate.

Response to Arguments

Applicant's arguments filed 1/16/04 have been fully considered but they are not persuasive. Applicants assert that Kanai teach gas gate means for preventing a film-forming raw material gas used in one vacuum vessel from dispersing into the other vacuum vessel, that is, for blocking the gas in one chamber from flowing into another.

Art Unit: 1763

Examiner argues the present claims do specify that "the substrate plate is treated in a chamber maintained under reduced pressure".

Conclusion

THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Parviz Hassanzadeh whose telephone number is (571)272-1435. The examiner can normally be reached on Tuesday-Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Gregory Mills can be reached on (571)272-1439. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Art Unit: 1763

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Parviz Hassanzadeh Primary Examiner Art Unit 1763

March 11, 2004